

ABSTRACT OF THE DISCLOSURE

An inspection device for photomasks and products fabricated using the same, capable of reducing the time from inspection to repair. A reference data generator generates reference data that is based on design data and includes sensitivity class codes that differentiate designated pattern functions such as signal lines and power supply lines by means of inspection sensitivity. Then an inspection sensitivity setter allocates the desired inspection sensitivity for each sensitivity class code. An image acquiring unit photographs a subject of inspection (e.g., photomask or wafer), and a comparator detects a defect by comparing the photographed image with the reference data. When a defect is found, a reference data extractor extracts the region of the reference data that corresponds to the defect location. A defect registration determinator refers to the sensitivity class codes for the region and determines whether to register the defect. This reduces the number of defects that are registered.